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**Supporting information for article:**

## **X-ray Characterization of Contact Holes for Block Copolymer Lithography**

**Daniel F. Sunday, Florian Delachat, Ahmed Gharbi, Guillaume Freychet, Christopher D. Liman, Raluca Tiron and R. Joseph Kline**

# X-ray Characterization of Contact Holes for Block Copolymer Lithography

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## Supplemental Information

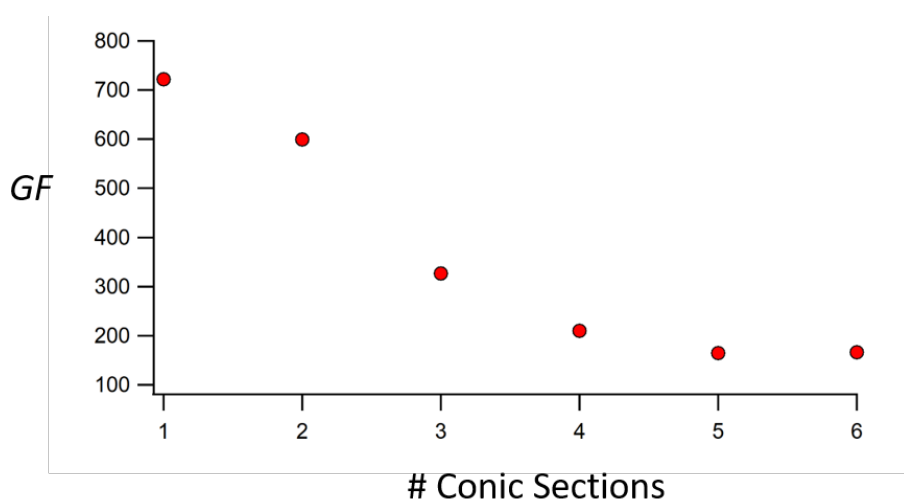


Figure S1: Progression in goodness of fit as a function of the number of conic sections for T-50

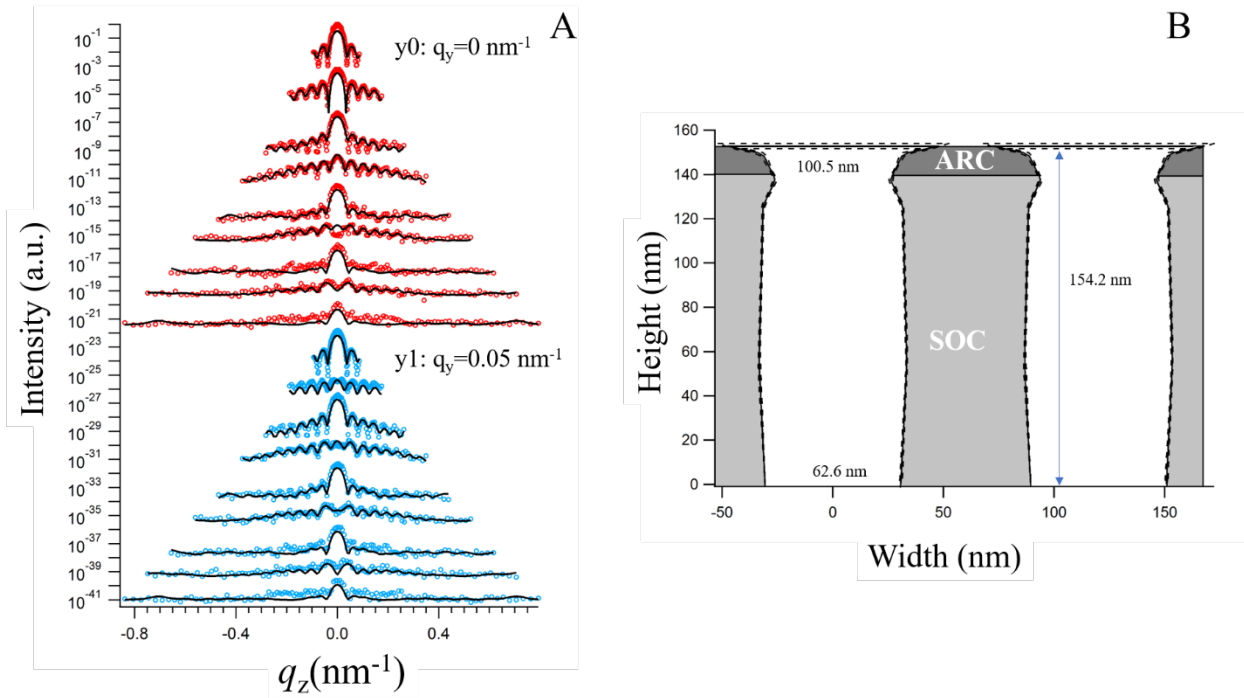


Figure S2 A) Simulated fit (solid line) to experimental data (colored circles) from 65-T for peak orders  $y_0$  and  $y_1$ , intensities are scaled for visual clarity. B) Structure of best fit to 65-T showing two unit cells, the white space represents the empty template, the lighter grey the SOC and the darker grey the ARC. The best fit to the bottom and top width are shown in the left unit cell. Dashed lines represent 95 % confidence intervals in the shape as determined by the MCMC algorithm.